

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A lithocell comprising:
 - a lithographic apparatus, comprising:
 - an illuminator configured to condition a beam of radiation,
 - a support structure configured to hold a patterning device, the patterning device configured to impart the beam with a pattern in its cross-section,
 - a substrate table configured to hold a substrate, and
 - a projection system configured to project the patterned beam onto a target portion of the substrate;
 - a track comprising one or more processing devices; and
 - a transport system, outside of the lithographic apparatus and the track, configured to transport the substrate along an elongate transporter pathway between the track and the lithographic apparatus, wherein the track and the lithographic apparatus are side by side along at least part of their respective long sides and the transport system extends along at least part of a short side of ~~the lithographic apparatus, or the track, or both the lithographic apparatus~~ and the track.
2. (Original) A lithocell according to claim 1, wherein the transport system comprises its own mini-environment.
3. (Previously Presented) A lithocell according to claim 1, wherein the transport system comprises a linear transporter pathway between the track and the lithographic apparatus.
4. (Original) A lithocell according to claim 1, wherein the transport system comprises at least two transporter pathways, one configured to transport the substrate from the track to the lithographic apparatus and one configured to transport the substrate from the lithographic apparatus to the track.

5. (Original) A lithocell according to claim 1, wherein the transport system comprises at least one transport robot configured to transport the substrate along the transporter pathway.
6. (Currently Amended) A lithocell according to claim 1, wherein the transport system is configured to serve ~~serves~~ a plurality of lithographic apparatuses.
7. (Previously Presented) A lithocell according to claim 1, comprising a plurality of tracks.
8. (Currently Amended) A lithocell according to claim 1, wherein the transport system is configured to serve ~~serves~~ a substrate process apparatus, a substrate metrology apparatus, or both, to form an extended substrate assembly line.
9. (Original) A lithocell according to claim 1, wherein the transport system is formable to a desired shape.
10. (Original) A lithocell according to claim 1, wherein the transport system comprises one or more transporter pathways configured to transport a substrate between different processing devices of the track.
11. (Previously Presented) A lithocell according to claim 1, wherein the transport system comprises a conveyor in the form of a shuttle on a linear guide actuated by an electric motor, or a pneumatic motor.
12. (Previously Presented) A lithocell according to claim 11, wherein the linear guide is a roller bearing guide or a gas bearing guide.
13. (Previously Presented) A lithocell according to claim 1, wherein the transport system comprises a conveyor belt configured to support the substrate transported thereon.
14. (Cancelled)
15. (Currently Amended) A lithocell comprising:

a lithographic apparatus, comprising:

an illuminator configured to condition ~~provide~~ a beam of radiation,
a support structure configured to hold a patterning device, the patterning device configured to impart the beam with a pattern in its cross-section,
a substrate table configured to hold a substrate, and
a projection system configured to project the patterned beam onto a target portion of the substrate;

a track comprising one or more processing devices; and

a transport system, external to the track and lithographic apparatus, configured to transport the substrate between the track and the lithographic apparatus, the transport system comprising a robot arm pivotable about an axis at its first end and adapted to hold a substrate at its opposite end, wherein the track and the lithographic apparatus are side by side along at least part of their respective long sides and the transport system extends along at least part of a short side of ~~the lithographic apparatus, or the track, or both the lithographic apparatus and~~ the track.

16. (Original) A lithocell according to claim 15, wherein the transport system comprises its own mini-environment.

17. (Currently Amended) A lithocell according to claim 15, wherein the transport system is configured to serve ~~serves~~ a plurality of lithographic apparatuses.

18. (Previously Presented) A lithocell according to claim 15, comprising a plurality of tracks.

19. (Original) A lithocell according to claim 15, wherein at least two lithographic apparatus and at least two tracks are disposed around the robot arm.

20. (Currently Amended) A lithocell according to claim 15, wherein the transport system is configured to serve ~~serves~~ a substrate process apparatus, a substrate metrology apparatus, or both, to form an extended substrate assembly line.

21. (Currently Amended) A device manufacturing method using a lithocell comprising a lithographic apparatus and a track comprising:

- applying a radiation-sensitive material to a substrate in the track;
- transporting the substrate to the lithographic apparatus from the track using a transporter between and external to them, wherein the track and the lithographic apparatus are side by side along at least part of their respective long sides and the transporter extends along at least part of a short side of ~~the lithographic apparatus, or the track, or both~~ the lithographic apparatus and the track; and
- projecting a patterned beam of radiation onto a target portion of the substrate.

22. (Original) A device manufacturing method according to claim 21, wherein the transporter is configured to transport the substrate along an elongate transporter pathway between the track and the lithographic apparatus.

23. (Original) A device manufacturing method according to claim 21, wherein the transporter, external to the track and lithographic apparatus, is configured to transport the substrate between the track and the lithographic apparatus by a robot arm pivotable about an axis at its first end and adapted to hold a substrate at its opposite end.

24. (Previously Presented) A lithocell according to claim 1, further comprising an automated material handling system configured to transport substrates to or from the lithographic apparatus or track independently from the transport system.